



02-07-02

Express Mail No. EU092835026US  
Attorney Docket No.: AM-5630.P1

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**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN RE APPLICATION OF: Chentsau Ying et al.

§ GROUP ART UNIT: Unknown

SERIAL NO.: 09/991,166

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§ EXAMINER: Unknown

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FOR: METHOD OF REDUCING PARTICULATES  
IN A PLASMA ETCH CHAMBER  
DURING A METAL ETCH PROCESS

§ Attorney Docket No.:

§ AM-5630.P1

Date: February 4, 2002

**INFORMATION DISCLOSURE STATEMENT  
TRANSMITTAL LETTER**

**Hon. Commissioner for Patents  
Washington, DC 20231**

Sir:


Applicants are submitting the subject Information Disclosure Statement under 37 CFR § 1.97(b)(1). This Information Disclosure Statement is being filed within three (3) months of the filing date of the subject application.

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**CERTIFICATE OF MAILING UNDER 37 CFR § 1.10**

I hereby certify that this paper is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as U.S. EXPRESS MAIL NO. EU092835026US in an envelope addressed to the: Commissioner for Patents, Box DD, Washington, DC 20231.

Date: February 4, 2002

  
Shirley L. Church, Reg. No. 31,858



Applicants do not believe that any fee is due in connection with the filing of this Information Disclosure Statement under 37 CFR § 1.97(b)(1). However, in the event that any additional fee is due, the Commissioner is hereby authorized to charge Deposit Account No. 50-1512 of Shirley L. Church, Sunnyvale, California, in the amount of such fee.

This transmittal letter is submitted in duplicate for accounting purposes.

Respectfully submitted,

A handwritten signature in cursive script that reads "Shirley L. Church".

Shirley L. Church  
Registration No. 31,858  
Attorney for Applicants

Correspondence Address:  
Patent Counsel  
Applied Materials, Inc.  
P.O. Box 450-A  
Santa Clara, California 95052

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

IN RE APPLICATION OF: Chentsau Ying et al.

SERIAL NO.: 09/991,166

FILED: November 16, 2001

FOR: METHOD OF REDUCING PARTICULATES  
IN PLASMA ETCH CHAMBER  
DURING A METAL ETCH PROCESS



§ GROUP ART UNIT: Unknown

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EXAMINER: Unknown

§ Attorney Docket No.:

§ AM-5630.P1

Date: February 4, 2002

**INFORMATION DISCLOSURE STATEMENT  
UNDER 37 CFR § 1.97(b)(1)**

**Hon. Commissioner for Patents  
Washington, DC 20231**

Sir:

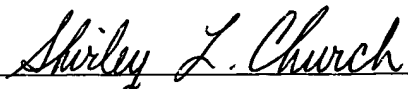
In accordance with 37 CFR § 1.97(b)(1), applicants hereby request consideration of this Information Disclosure Statement. This Information Disclosure Statement is being filed within three (3) months of the filing date of the subject application. Applicants are providing herewith a copy of each document cited on the attached Form PTO-1449.

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**CERTIFICATE OF MAILING UNDER 37 CFR § 1.10**

I hereby certify that this paper is being deposited with the U.S. Postal Service on the date shown below with sufficient postage as U.S. EXPRESS MAIL NO. EU092835026US in an envelope addressed to the: Commissioner for Patents, Box DD, Washington, DC 20231.

Date: February 4, 2002

  
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Shirley L. Church, Reg. No. 31,858

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The submission of this Information Disclosure Statement and Form PTO-1449 is not an admission that the art cited is "prior art" with respect to the present invention, nor is it a representation that no better art exists. Applicants hereby reserve the right to swear behind or otherwise disprove any alleged "prior" nature of any art cited should the facts support and the situation warrant such an action.

If the Examiner has any questions, he is respectfully requested to contact the undersigned attorney at the telephone number set forth below.

Respectfully submitted,

Shirley L. Church  
Registration No. 31,858  
Attorney for Applicants  
(408) 245-5109

Correspondence Address:  
Patent Counsel  
Applied Materials, Inc.  
P.O. Box 450-A  
Santa Clara, California 95052

FORM PTO-1449  
(Equivalent)

U.S. Department of Commerce  
Patent and Trademark Office

U.S. Application Serial No.  
09/991,166

Atty. Docket No.  
AM-5630.P1

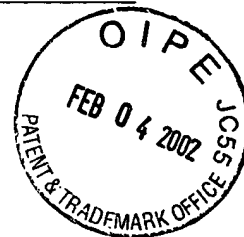
INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT

(Use several sheets if necessary)

Chentsau Ying et al.  
Applicants

November 16, 2001  
Filing Date

Unknown  
Group



U. S. PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Issue Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Filing Date If Appropriate</u>
_____	5,811,356	09/22/98	Muruges et al.	438	711	
_____	5,824,375	10/20/98	Gupta	427	569	
_____	6,020,035	02/01/00	Gupta et al.	427	534	
_____	6,103,055	08/15/00	Maher et al.	156	345	
_____	6,121,161	09/19/00	Rossmann et al.	438	783	
_____	6,143,078	11/07/00	Ishikawa et al.	118	715	

FOREIGN PATENT DOCUMENTS

<u>Examiner Initial</u>	<u>Document Number</u>	<u>Publication Date</u>	<u>Name</u>	<u>Class</u>	<u>Subclass</u>	<u>Translation If Appropriate</u>
_____	EP 0892083	01/20/99	Qiao et al.	C23C	16/44	

Examiner \_\_\_\_\_ Date Considered \_\_\_\_\_

Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

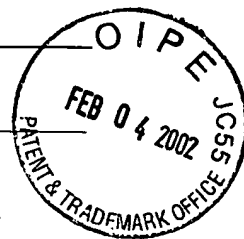
\* Provided by the Applicant.

\*\* Cited in the specification by Applicant.

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

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\_\_\_\_ J. Hughes et al., "Dry Etch Sequencing Induced Gate Oxide Degradation due to Metallic Contamination in 0.25  $\mu$ m CMOS Manufacturing", *International Electronic Devices Meeting*, pp.337-340 (1998).

\_\_\_\_ K. K. Singh et al., "Residual CF<sub>x</sub> Radicals From Periodic Dry Cleans of Ar<sup>+</sup> Sputter Etch Chamber: Causes and Process Consequences", *Electrochemical Society Proceedings*, Vol. 31, pp.182-189 (1997).

\_\_\_\_ S. Tehrani et al., "Progress and Outlook for MRAM Technology", *IEEE Transactions on Magnetics*, Vol. 35, No. 5, pp.2814-2819. (Sept 1999).

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Examiner

Date Considered

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Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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